

# Probe Needle Wear and Contact Resistance

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# Participants

- **SEMATECH**
  - Probes PTAB
- **Probe Needles**
  - Advanced Probing Systems, Inc.
- **Probe Cards**
  - CerProbe Corporation
  - JEM America
  - Micro-Probe, Inc.
  - Probe Technology Corporation
  - Wentworth Laboratories
- **Testing Facilities**
  - Applied Precision, Inc. (John Strom, Kenneth Sokol, Bryce Ekstrom)
  - Sandia National Laboratories (David Monroe, Scot Swanson)

# Research Objectives

- **No Benchmarking**
  - Probe card construction was specified for this study
  - Overall performance between cards **WAS NOT** compared
- **Quantify abrasive cleaning effects**
  - Probe tip wear due to burnishing
  - Appropriate cleaning procedures
- **Evaluate probe needle wear behavior**
  - Room and elevated temperature touchdown testing
  - Appropriate probe needle metal system

# Research Focus

- **SEMATECH 1997 Development Roadmap**
  - Room temperature (*hot chuck at 30°C*)
  - Elevated temperature (*hot chuck at 85°C*)
- **“Practice” for probe card cleaning**
  - 3- $\mu\text{m}$  grit burnishing pad (*hot chuck at 30°C*)
- **“Practices” used for 70  $\mu\text{m}$  pitch probe cards**
  - Tungsten and tungsten-rhenium probe materials
  - 0.005” and 0.007” diameter probe needles
  - Three-tiered epoxy ring probe cards
  - **For this presentation only Tier 1 behavior will be discussed**

# Probe Needles

- **Testing Environments**

- Abrasive cleaning
- Room temperature(30°C)
- High temperature (85°C)
- “Low” forcing current (50 mA)

- **Focus on “Primary” Probe Needle Properties**

- Material
- Probe and probe tip diameter
- Etch length

# Probe Card

- **Consistent “Secondary” Probe Needle Variables**

- Balanced contact force
- Overtravel
- Beam angle
- Tip angle
- Etc....

# Probe Needle Specifications

## ● Isolinear™ Probe Needles

- Known probe tip geometry
- Tip diameter and length mathematically related

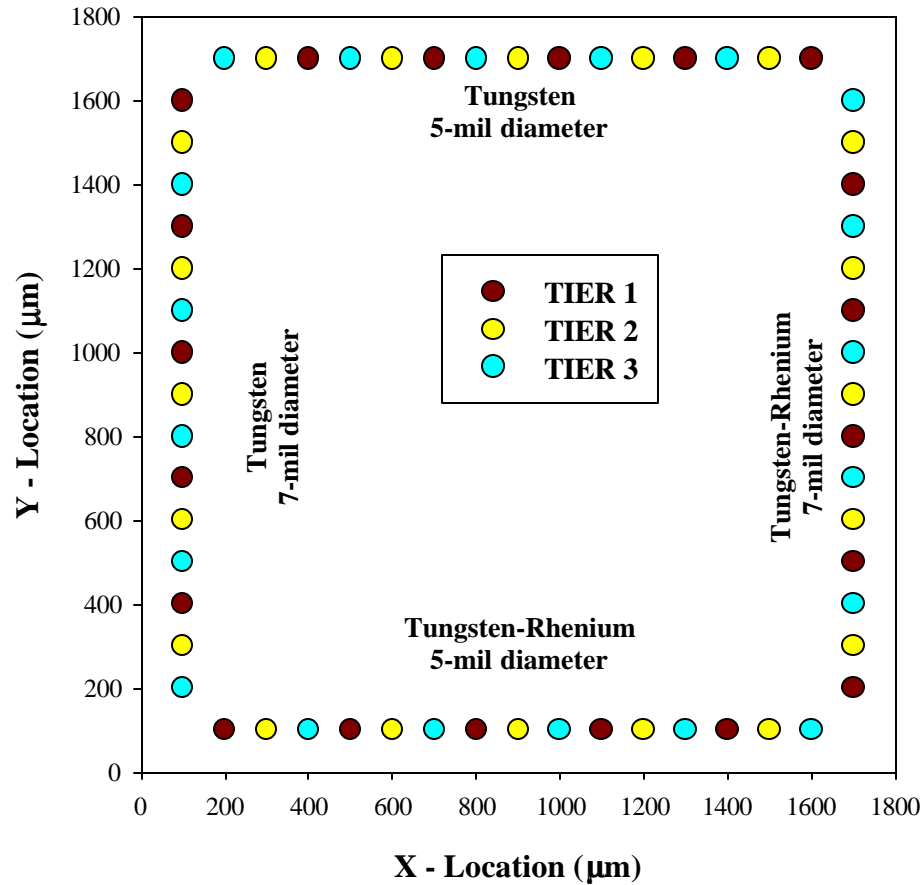
Probe Needle	Etch Length (inch)	Etch "Rate" (deg)	Finish
5-mil Diameter	0.070	4.1	Tungsten (W): Matte
	0.080	3.6	Tungsten-Rhenium (WRe): Polish
	0.090	3.2	
7-mil Diameter	0.090	4.5	Tungsten (W): Matte
	0.100	4.0	Tungsten-Rhenium (WRe): Polish
	0.110	3.6	

# Probe Card Specifications

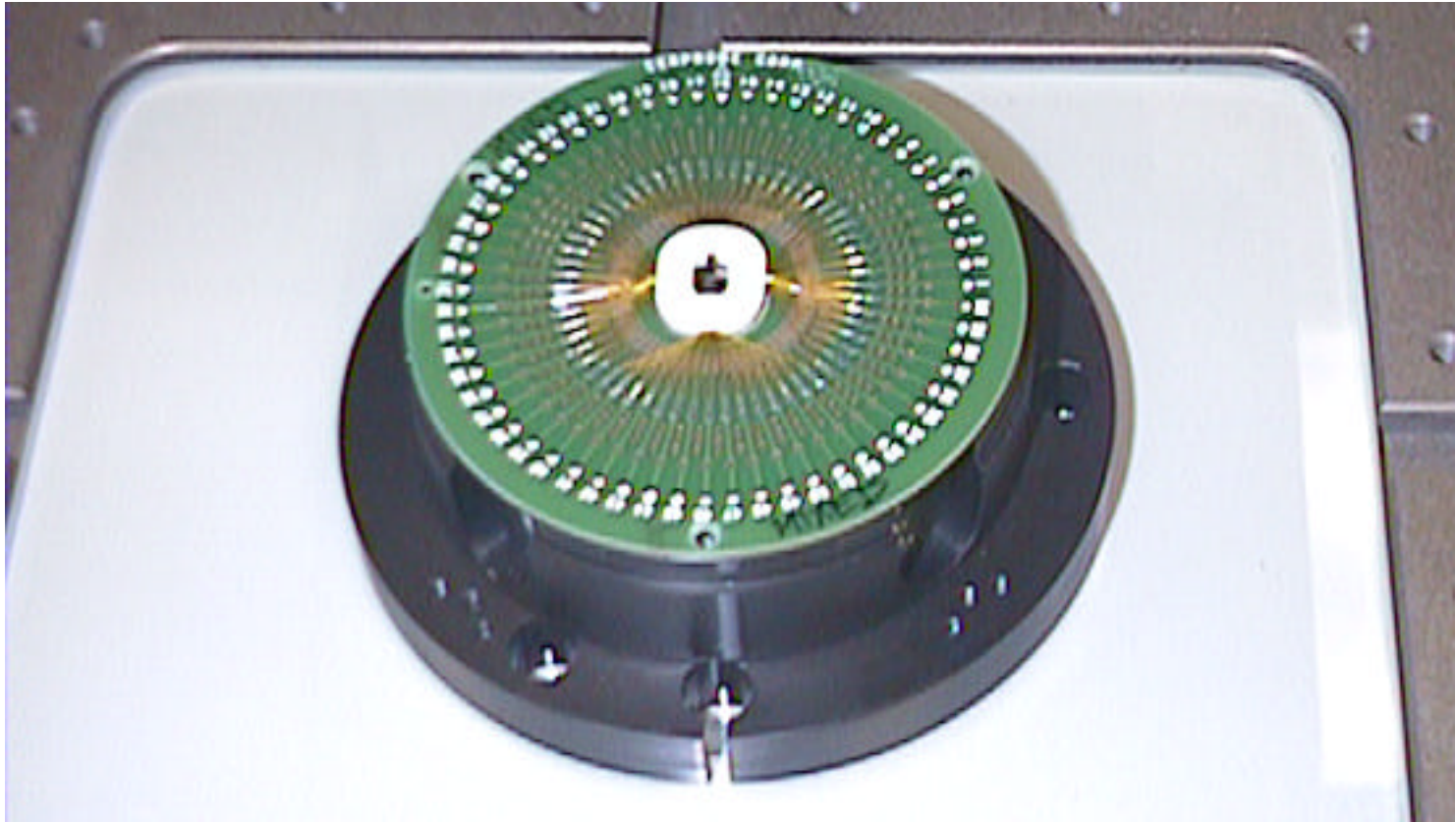
<b>Board Style:</b>	HP 4062, 4" PCB	<b>Probe Depth:</b>	150 mils
<b>Test Temperature:</b>	25° to 85°C	<b>Ring Material:</b>	<i>Ceramic</i>
<b>Tip Diameter:</b>	1.2 ± 0.1 mils	<b>Overdrive:</b>	3 mils
<b>Tip Shape:</b>	Flat	<b>Planarity:</b>	± 0.5 mils
<b>Tip Angle:</b>	103 ± 3 deg.	<b>Alignment:</b>	± 0.5 mils
<b>Beam Angle:</b>	10 deg.	<b>Leakage:</b>	100 nA
<b>Pad Material:</b>	Aluminum	<b>Contact Resistance</b>	1.5 to 2.0 Ω
<b>Fanout:</b>	0 ± 3 deg.	<b>Gram Force:</b>	2 grams/mil
		<b>BCF:</b>	± 20%



# 60-Pin Configuration



# Probe Card



**SEMATECH**  
**Advanced Probing Systems, Inc.**

**SWTW '98**

**Applied Precision, Inc.**  
**Sandia National Labs**

# Test Wafers

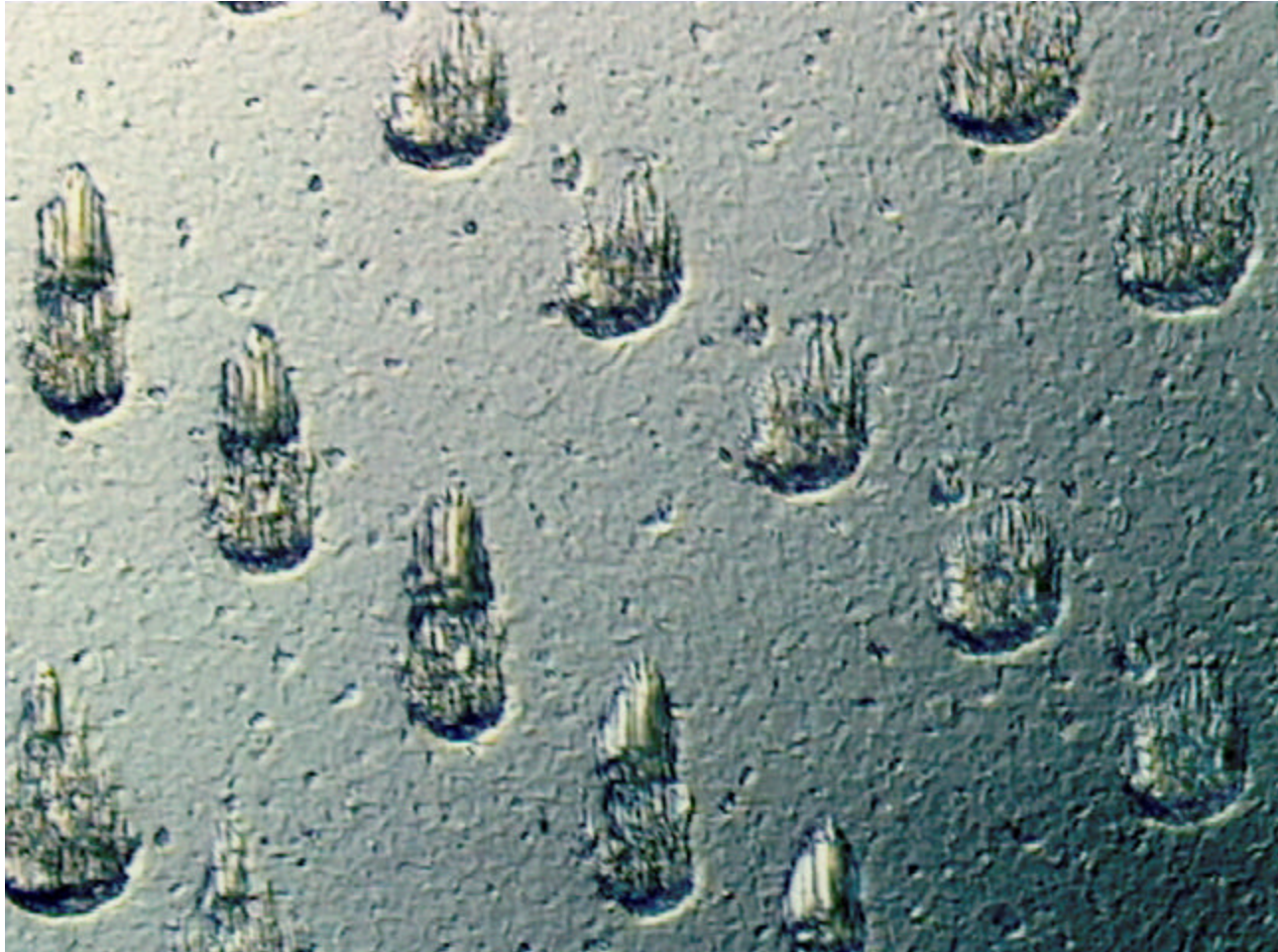
- **Abrasive Testing**

- 6-inch “scrap” metallized wafer
- 3- $\mu\text{m}$  abrasive pad , i.e. “the pink stuff”

- **Touchdown Testing**

- 8-inch metallized wafer manufactured by SEMATECH
- Titanium-nitride substrate
- 1- $\mu\text{m}$  thick Aluminum layer

# Stepping Pattern



**SEMATECH**  
**Advanced Probing Systems, Inc.**

**SWTW '98**

**Applied Precision, Inc.**  
**Sandia National Labs**

# Test Equipment

- **ElectroGlas-4080 Tester with “Hot Chuck”**
  - Burnishing pad touchdown testing
  - Metallized wafer touchdown testing at 30°C and 85°C
- **HP4062 Parametric 48-Channel Analyzer**
  - On-line contact resistance measurements
- **Applied Precision PRVX<sub>2</sub> -Probe Card Analyzer**
  - Probe tip diameter
  - Contact resistance
  - Balanced contact force

# Touchdown “Test Flow”

## ● 3- $\mu\text{m}$ Abrasive Pad

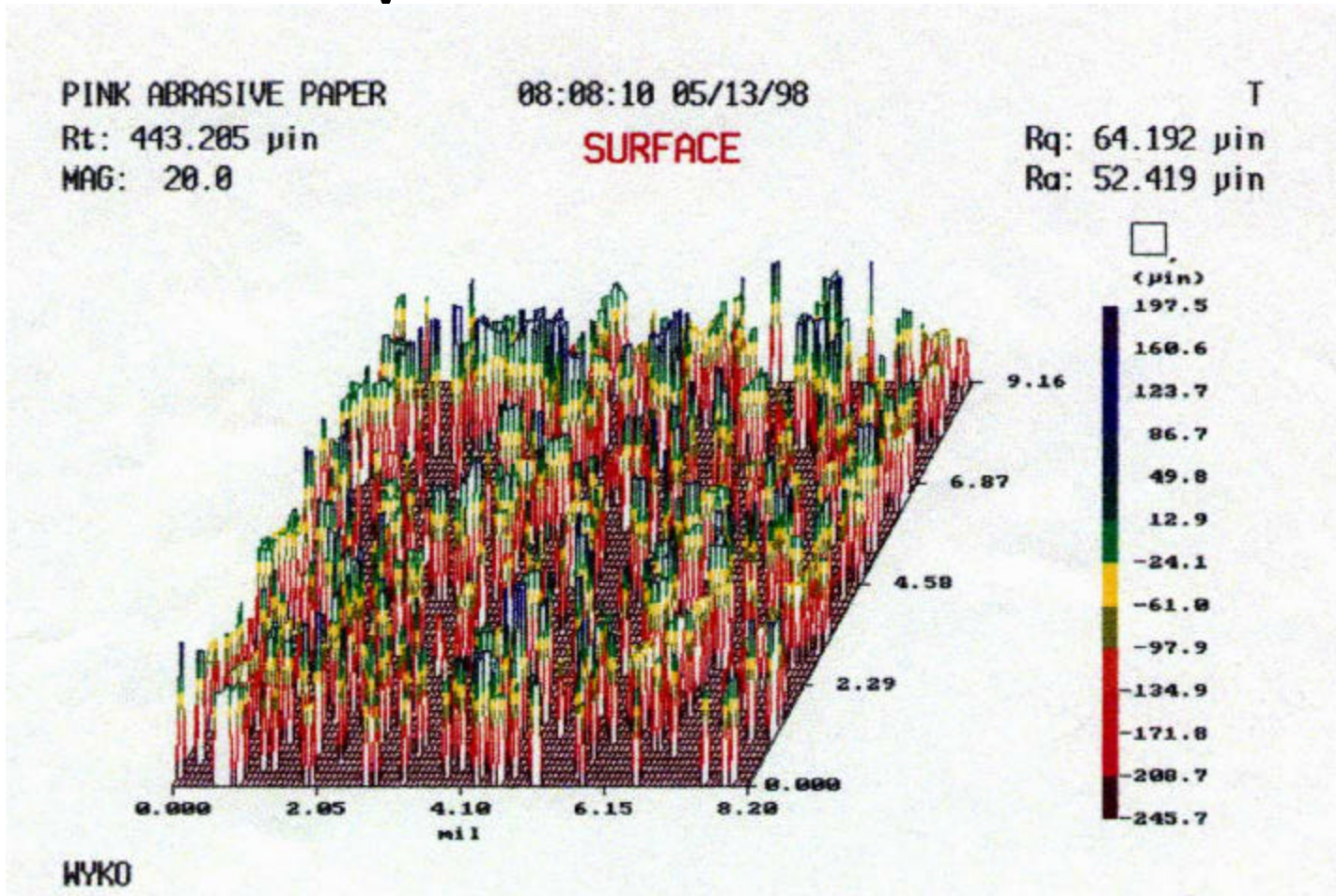
- 3.0-mil overtravel, linear mode, double-touchdown mode
- PRVX<sub>2</sub> metrology performed after 0, 7.5K, and 15K touchdowns
  - Contact resistance
  - Tip diameter

## ● Metallized Wafer at 30° and 85°C

- 3.0 mil overdrive, double-touchdown mode (8 touchdowns/second)
- Contact resistance measurements every 5K touchdowns
- PRVX<sub>2</sub> metrology performed after 0, 250K, and 500K touchdowns
  - Contact resistance
  - Tip diameter



# 3- $\mu\text{m}$ Abrasive Pad



# 3- $\mu\text{m}$ Abrasive Pad

## ● Tungsten vs. Tungsten-Rhenium

- Abrasive particles are considerably harder than both probe materials
- No “significant” differences between materials in amount of tip length removed

## ● 5-mil vs. 7-mil Diameter Probe Needles

- Amount of tip length removed from the 5-mil probes was greater than that of the 7-mil probes

## ● Contact Resistance Measurements

- Baseline (“as delivered”) and post-touchdown  $C_{\text{RES}}$  values were higher than expected
- Cleaning was performed and  $C_{\text{RES}}$  values were considerably reduced
- Contamination on probe tip surface - tungsten-oxide? other residue?



# 3- $\mu\text{m}$ Abrasive Pad

- **“Approximate” Wear Rates**

- Changes in tip geometry occur with each touchdown
- **Wear rate =  $f(\text{overtravel, scrub length, BCF, etch length, contact materials})$**
- Conservative “first approximation” of abrasive wear rates

	<b>“Estimated” amount of material removed 0 to 7.5K</b>	<b>“Estimated” amount of material removed 0 to 15K</b>
<b>5-mil diameter</b>	<b>38 Å per touchdown</b>	<b>52 Å per touchdown</b>
<b>7-mil diameter</b>	<b>35 Å per touchdown</b>	<b>48 Å per touchdown</b>

# Al-Wafer at 30° and 85°C

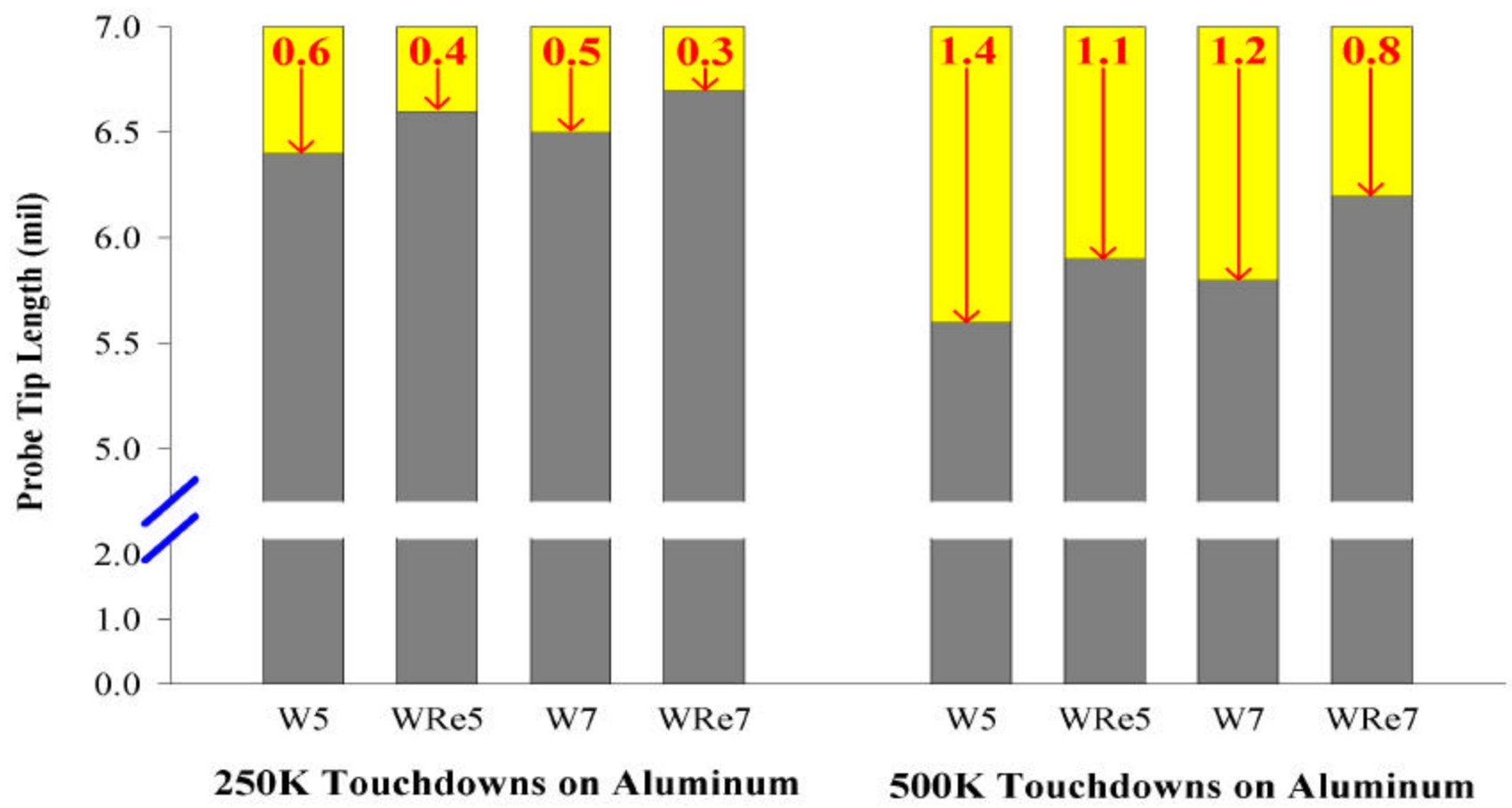
## ● Probe Tip Wear Characteristics

- Isolinear™ taper shape was used to calculate average tip length changes

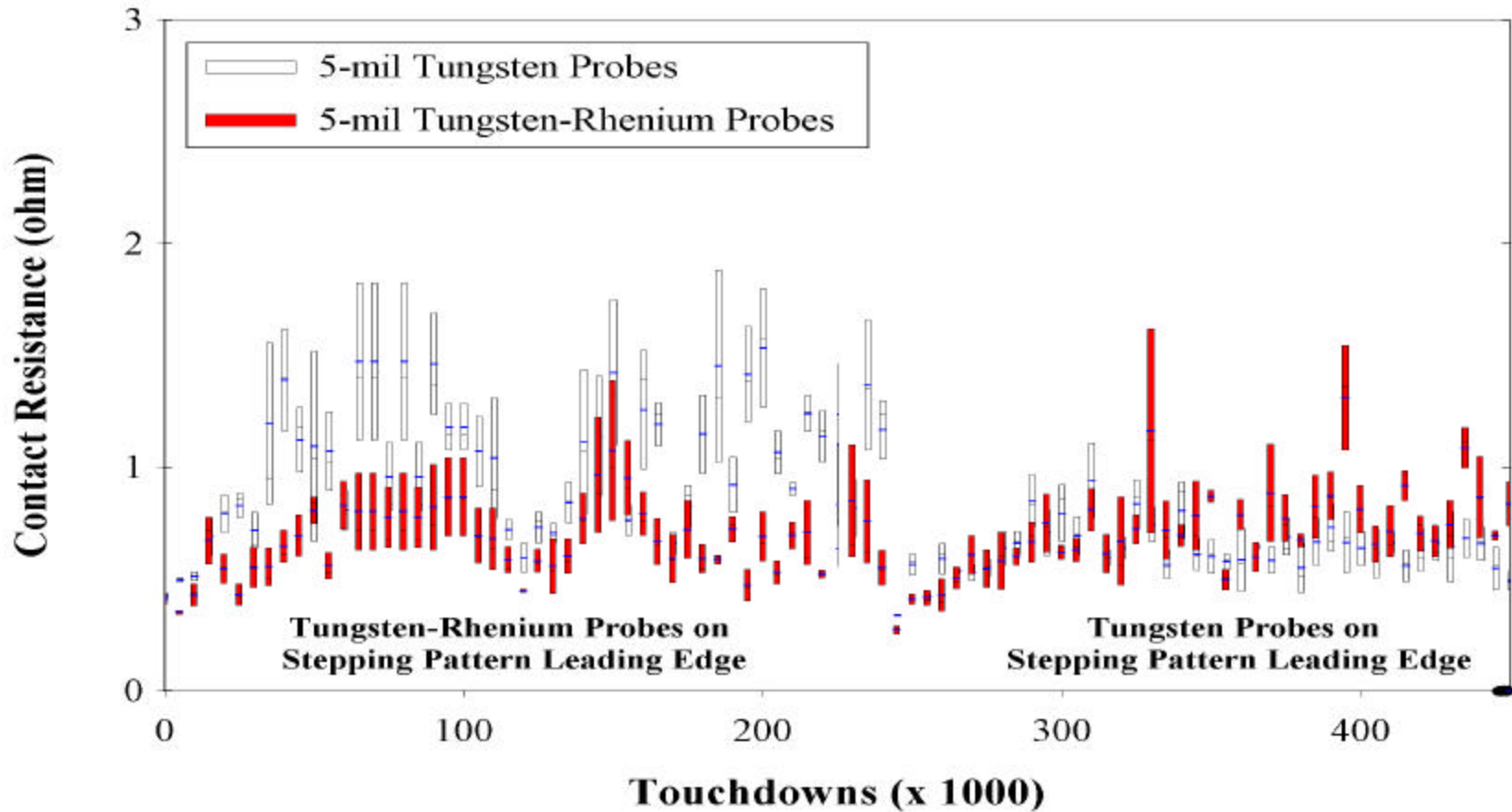
## ● Contact Resistance

- Box plots were used to show the range and mean of  $C_{RES}$  values for material

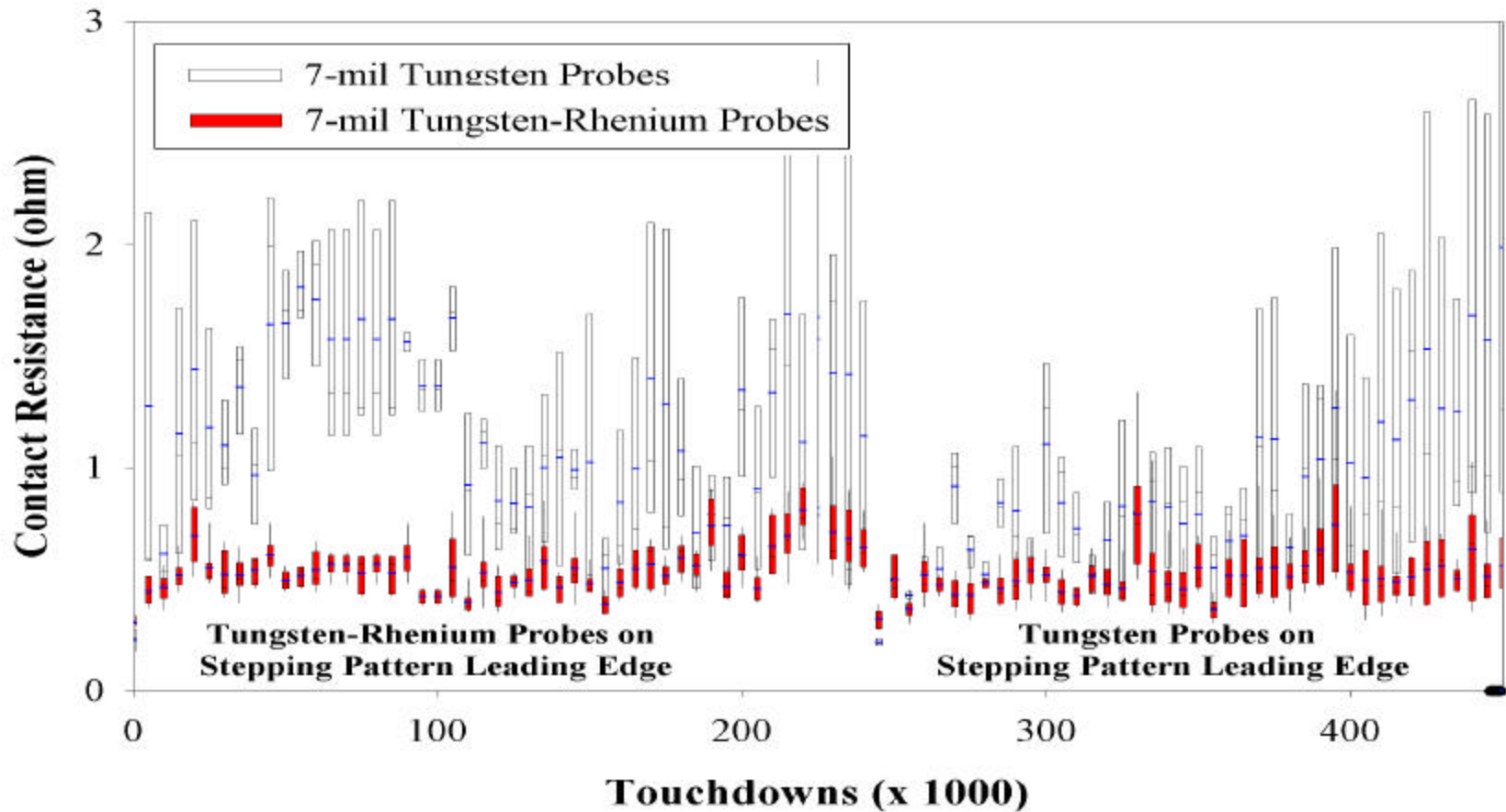
Probe needle tip length (Tier 1 design specification = 7-mil)  
 Material worn away by touchdown on aluminum at 30 °C with 3-mil overdrive



# Tier 1 Contact Resistance on Wafer (3-mil overtravel at 30°C)



## Tier 1 Contact Resistance on Wafer (3-mil overtravel at 30°C)



# Al-Wafer at 30°C

## ● Wear and $C_{RES}$

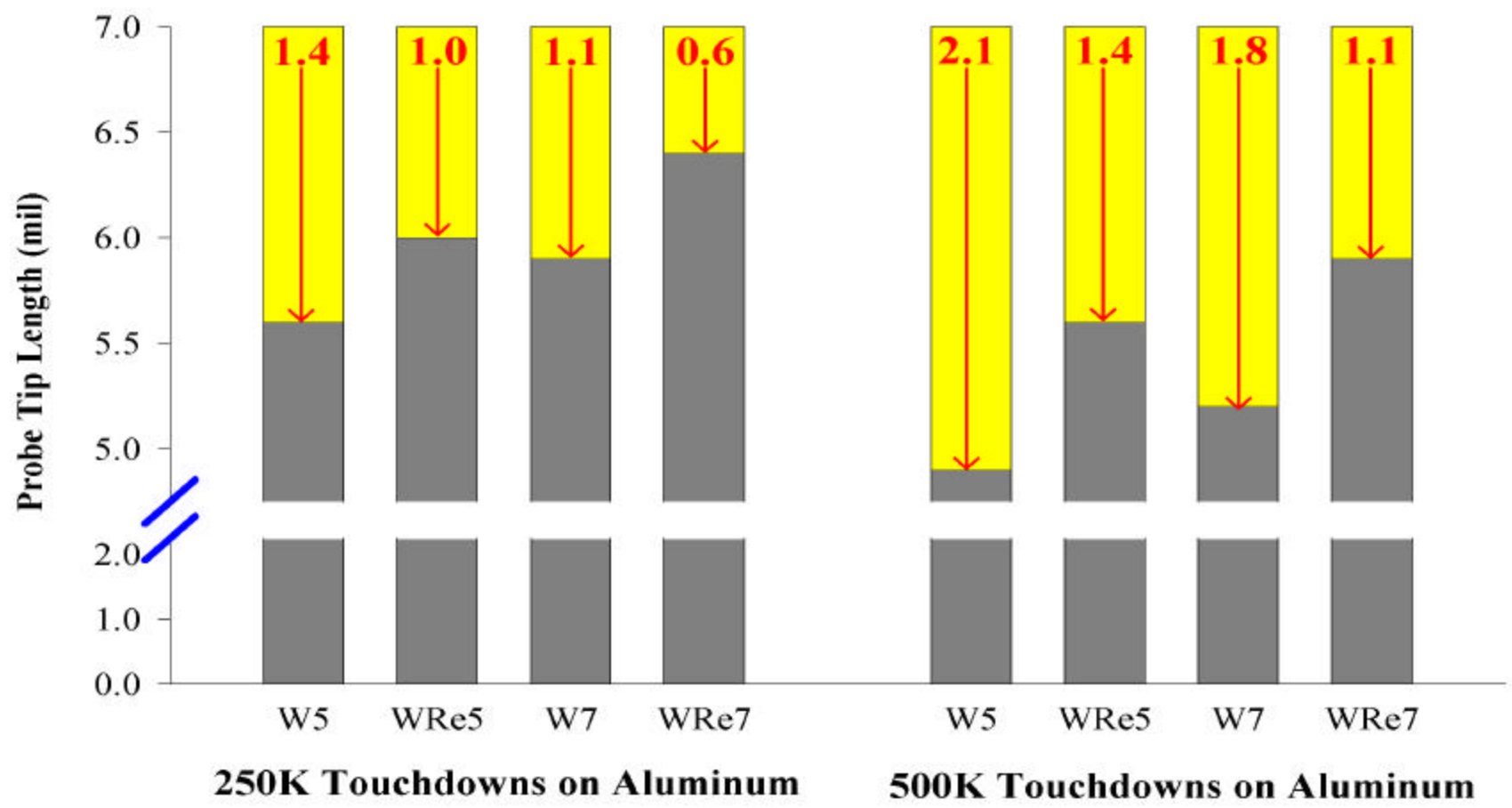
- 7-mil WRe-probes demonstrated significantly lower  $C_{RES}$  values than 7-mil W-probes
- Differences between the 5-mil probes were not as significant
- Microhardness values of the probes

	W005	WRe005	W007	WRe007
VHN (kg/mm <sup>2</sup> )	738 ± 47	736 ± 33	718 ± 45	804 ± 23

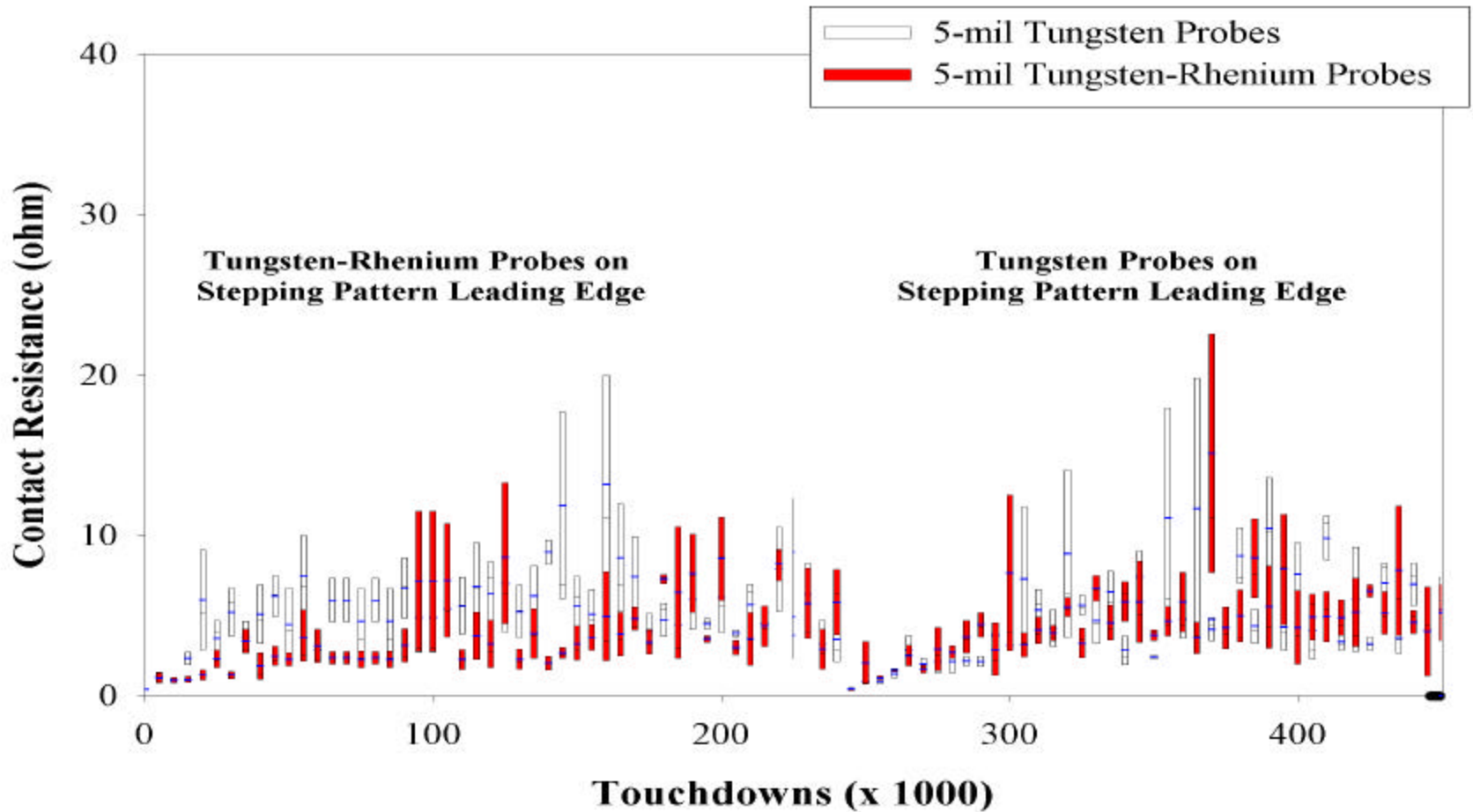
## ● $C_{RES}$ on “Virgin” vs. “Scrubbed” Aluminum

- $C_{RES}$  response of the WRe-probes unaffected by wafer surface condition
- On the other hand, the W-probes demonstrated marked differences

Probe needle tip length (Tier 1 design specification = 7-mil)  
 Material worn away by touchdown on aluminum at 85 °C with 3-mil overdrive

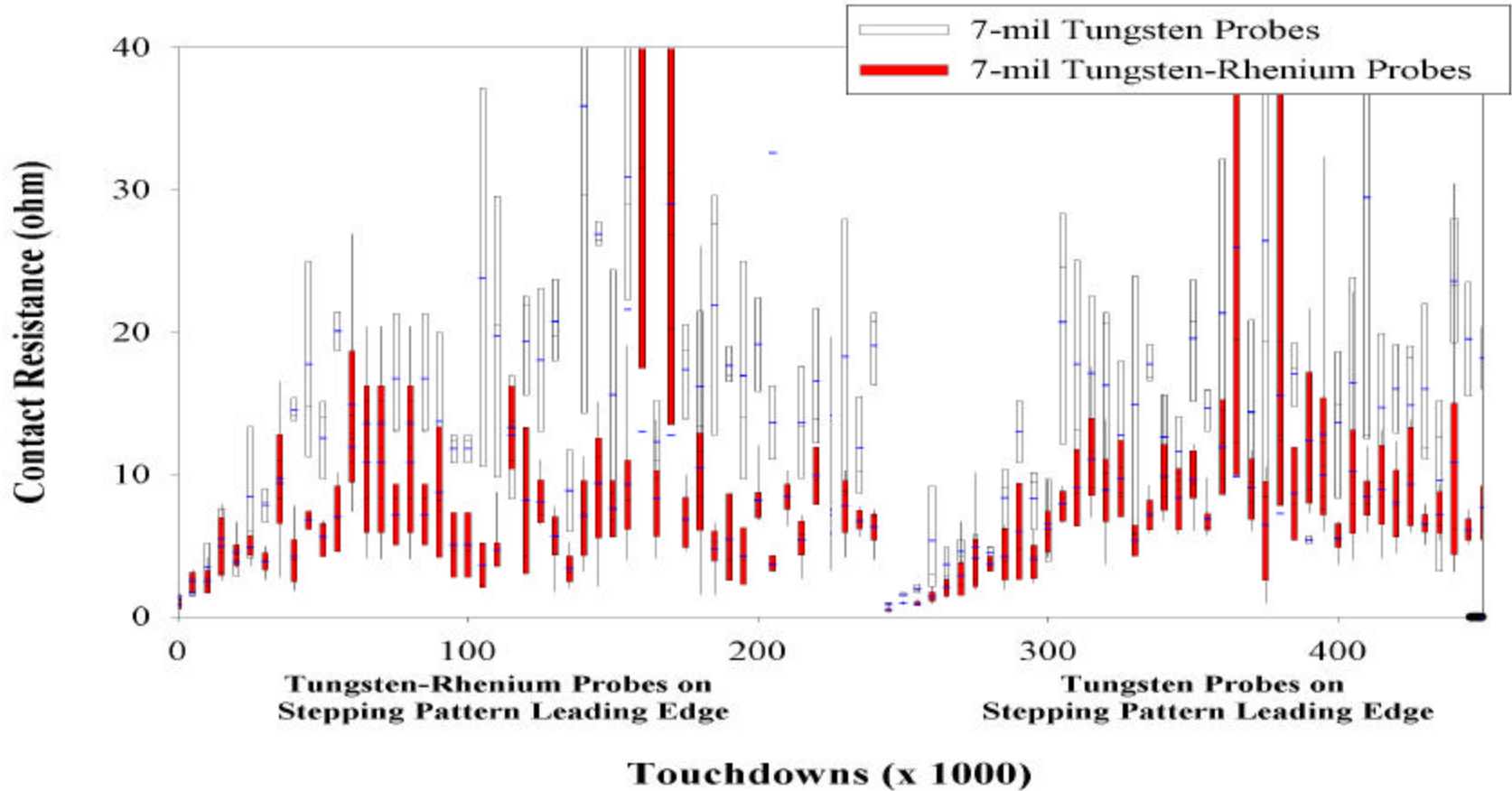


# Tier 1 Contact Resistance on Wafer (3-mil overtravel at 85°C)





## Tier 1 Contact Resistance on Wafer (3-mil overtravel at 85°C)



# Al-Wafer at 85°C

- **Wear and  $C_{RES}$**

- Reductions in WRe-probe tip lengths were significantly less than those of the W-probes
- Overall, the WRe-probes demonstrated lower and “more stable”  $C_{RES}$  behavior

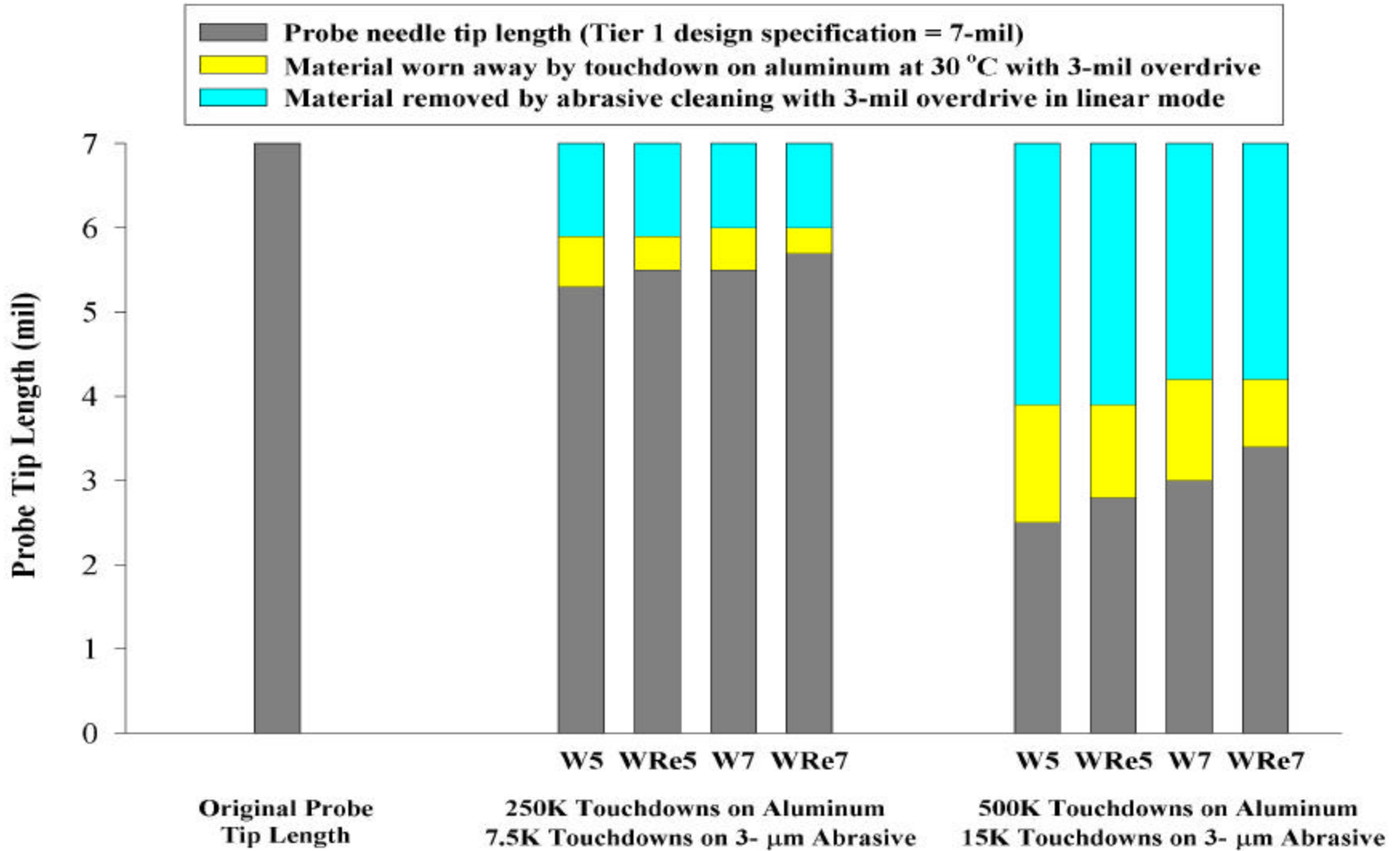
- **Temperature Effects**

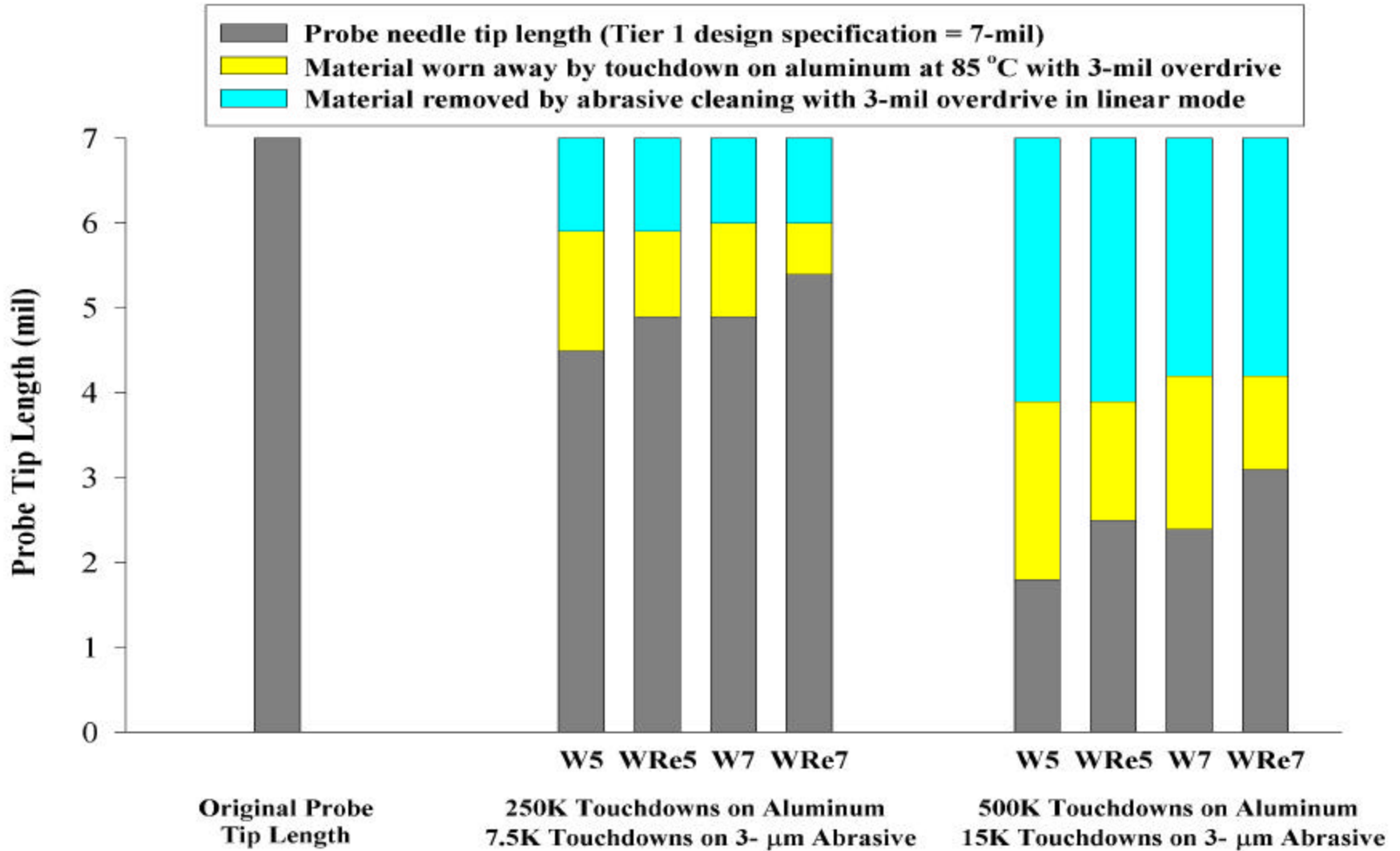
- Metallurgical fact - materials soften with increased temperature
- Rhenium stabilizes small diameter wire grain structure at high temperatures
- Grain structure affects hardness and wear characteristics of probe needles
- The “softening rate” of WRe-probes differs from than that of W-probes

# Application of Results

## “A Thought Experiment”

- **Probe card required to test 500K die**
- **Testing performed at room and high temperature**
- **“Triple Hit” cleaning every 100 die**
  - 7.5K cleaning touchdowns after 250K die
  - 15K cleaning touchdowns after 500K die
- **Can an estimate be made of the probe service life?**
  - Reduction in tip length
  - Increase in tip diameter





# Summary

## TIER 1 ONLY

- **No Benchmarking**
- **Probe Needle Wear**
  - Abrasive Cleaning
    - Cleaning pad material is dramatically harder than both probe materials
    - No significant differences in the amount of tip length removed
    - Wear rate “first approximations” based on 15K cleanings: 52 and 48 Å per touchdown for 5-mil and 7-mil probes, respectively
    - Wear rate =  $f(\text{overtravel, scrub length, BCF, etch length, contact materials})$

# Summary

## ● Probe Needle Wear

– Aluminum-wafer at 30°C

- Difference in wear behavior were observed for the 7-mil probes and not as severe for the 5-mil probes
- Wear rate “first approximations” based on 500K touchdowns: 700, 560, 600, and 380 Å per 1K-touchdowns for W005, WRe005, W007, and WRe007, respectively
- Hardness values of the 7-mil WRe-probes were significantly higher than those of the W-probes
- The 5-mil probes had comparable hardness values and hence demonstrated similar wear characteristics
- As the diameter of the probe needles decreases, the hardness of tungsten and tungsten-rhenium become similar

# Summary

## ● Probe Needle Wear

– Al-Wafer at 85°C

- Wear differences were exacerbated by the higher temperature
- Wear rate “first approximations” based on 500K touchdowns: 1100, 700, 900, and 560 Å per 1K-touchdowns for W005, WRe005, W007, and WRe007, respectively
- Increased temperature results in a thicker Al-oxide layer and a reduction in the probe needle hardness
- Changes of the WRe-probe tip lengths were significantly less than those of the W-probes
- Alloying with rhenium stabilizes the grain structure and hardness at high temperatures
- The temperature dependent “softening” of WRe-probes is different than that of W-probes



# Summary

## ● Contact Resistance

- Al-Wafer at 30°C
  - $C_{RES}$  consistency of the W-probes was affected by the wafer surface condition
  - W-probes demonstrated higher  $C_{RES}$  values on the “scrubbed” portion
  - WRe-probes demonstrated consistent  $C_{RES}$  values regardless of the wafer surface, i.e. “virgin” vs. “scrubbed”
- Al-Wafer at 85°C
  - $C_{RES}$  variance of all probe needles was greater at higher temperature
  - $C_{RES}$  consistency of the W-probes was affected by the wafer surface condition; but not as dramatically as at room temperature
  - $C_{RES}$  behavior of the WRe-probes was unaffected by the wafer surface condition
  - Overall, the WRe-probes demonstrated lower and consistent  $C_{RES}$  values

# Summary

## ● Probe Service Life Estimates

- “First approximations of the service life” for Tier 1 were made
- Differences in probe tip wear are over-shadowed by abrasive cleaning
- Service Life =  $f(\text{temperature, current, overtravel, scrub length, BCF, cleaning frequency, and contact material})$
- The results indicate that WRe-probes would provide a longer service life than W-probes at high temperatures

## ● Benefits of Tungsten-Rhenium

- At room temperature, WRe-probes provide  $C_{RES}$  consistency with slight improvements in wear that over-shadowed by abrasive cleaning
- At high temperature, WRe-probes provide  $C_{RES}$  consistency and significant improvements in wear

# Side Bar

## ● Additional Observations

- $C_{RES}$  values of probes that never touched a wafer were higher than expected
- Cleaning was performed and  $C_{RES}$  values were considerably reduced
- Contamination on probe tip surface - tungsten-oxide? other residue? who really knows?

## ● Future Work

- Analysis of Tier 2 and Tier 3 behavior